

=> s polybenzazole# and light-resist?

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      113 POLYBENZAZOLE#
      788669 LIGHT
      945548 RESIST?
      3284 LIGHT-RESIST?
          (LIGHT(W) RESIST?)
L1      1 POLYBENZAZOLE# AND LIGHT-RESIST?

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=> d

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L1  ANSWER 1 OF 1  USPATFULL
AN  1999:155347  USPATFULL
TI  Polybenzazole fiber and method for production thereof
IN  Teramoto, Yoshihiko, Ohtsu, Japan
    Kitagawa, Tooru, Ohtsu, Japan
    Tanaka, Yoshikazu, Ohtsu, Japan
    Ishitobi, Michio, Ohtsu, Japan
PA  Toyo Boseki Kabushiki Kaisha, Japan (non-U.S. corporation)
PI  US 5993963  19991130
AI  US 1997-940780  19970930 (8)
PRAI JP 1996-260895      19961001
DT  Utility
LN.CNT 564
INCL  INCLM: 428/364.000
      INCLS: 428/394.000
NCL   NCLM: 428/364.000
      NCLS: 428/394.000
IC    [6]
      ICM: D02G003-00
EXF   428/357; 428/364; 428/394; 428/359

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=> s polybenzazole# and regular reflectance#

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      113 POLYBENZAZOLE#
      143337 REGULAR
      24067 REFLECTANCE#
          23 REGULAR REFLECTANCE#
              (REGULAR(W) REFLECTANCE#)
L2      0 POLYBENZAZOLE# AND REGULAR REFLECTANCE#

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=> s polybenzazole# and reflectance#

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      113 POLYBENZAZOLE#
      24067 REFLECTANCE#
L3      2 POLYBENZAZOLE# AND REFLECTANCE#

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=> s polybenzazole# and wavelength#

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      113 POLYBENZAZOLE#
      151152 WAVELENGTH#
L4      8 POLYBENZAZOLE# AND WAVELENGTH#

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=> d 13 1-2

L3 ANSWER 1 OF 2 USPATFULL  
AN 1999:33748 USPATFULL  
TI Photocurable formulation containing a partially polymerized  
divinylsiloxane linked bisbenzocyclobutene resin  
IN Foster, Pamela S., Midland, MI, United States  
Ecker, Ernest L., Midland, MI, United States  
Rutter, Jr., Edward W., Midland, MI, United States  
Moyer, Eric S., Midland, MI, United States  
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)  
PI US 5882836 19990316  
AI US 1995-465664 19950605 (8)  
RLI Division of Ser. No. US 1994-224203, filed on 14 Apr 1994 which is a  
continuation-in-part of Ser. No. US 1993-54999, filed on 29 Apr 1993  
DT Utility  
LN.CNT 1491  
INCL INCLM: 430/194.000  
INCLS: 430/286.100; 430/287.100; 522/065.000; 522/099.000  
NCL NCLM: 430/194.000  
NCLS: 430/286.100; 430/287.100; 522/065.000; 522/099.000  
IC [6]  
ICM: G03C001-52  
ICS: C08C002-48  
EXF 430/286; 430/287; 430/286.1; 430/287.1; 430/194; 522/99; 522/65  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L3 ANSWER 2 OF 2 USPATFULL  
AN 1998:162564 USPATFULL  
TI Partially polymerized divinylsiloxane linked bisbenzocyclobutene resins  
and methods for making said resins  
IN Foster, Pamela S., Midland, MI, United States  
Ecker, Ernest L., Midland, MI, United States  
Rutter, Jr., Edward W., Midland, MI, United States  
Moyer, Eric S., Midland, MI, United States  
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)  
PI US 5854302 19981229  
AI US 1994-224203 19940414 (8)  
RLI Continuation-in-part of Ser. No. US 1993-54999, filed on 29 Apr 1993,  
now abandoned  
DT Utility  
LN.CNT 1506  
INCL INCLM: 522/172.000  
INCLS: 526/281.000; 528/032.000; 556/453.000  
NCL NCLM: 522/172.000  
NCLS: 526/281.000; 528/032.000; 556/453.000  
IC [6]  
ICM: C08F002-46  
ICS: C08F010-08; C08G077-20  
EXF 522/172; 526/281; 528/32; 556/453; 428/391  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

=> d 14 1-8

L4 ANSWER 1 OF 8 USPATFULL  
AN 2000:84002 USPATFULL  
TI Photodefineable cyclobutarene compositions  
IN Oaks, Frank L., San Carlos, CA, United States  
Moyer, Eric S., Midland, MI, United States

Rutter, Jr., Edward W., Midland, MI, United States  
Harris, Robert F., Midland, MI, United States  
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)  
PI US 6083661 20000704  
AI US 1994-290197 19940815 (8)  
RLI Continuation-in-part of Ser. No. US 1991-805395, filed on 10 Dec 1991,  
now abandoned  
DT Utility  
LN.CNT 2011  
INCL INCLM: 430/286.100  
INCLS: 430/194.000; 430/287.100; 522/065.000; 522/099.000  
NCL NCLM: 430/286.100  
NCLS: 430/194.000; 430/287.100; 522/065.000; 522/099.000  
IC [7]  
ICM: G03C001-13  
EXF 430/286; 430/287; 430/194; 522/160; 428/195  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L4 ANSWER 2 OF 8 USPATFULL  
AN 2000:34296 USPATFULL  
TI **Polybenzazole** fiber having high tensile modulus and process of  
manufacture thereof  
IN Kitagawa, Tooru, Ohtsu, Japan  
Ishitobi, Michio, Ohtsu, Japan  
PA Toyo Boseki Kabushiki Kaisha, Osaka-fu, Japan (non-U.S. corporation)  
PI US 6040050 20000321  
AI US 1998-97997 19980616 (9)  
PRAI JP 1997-161554 19970618  
JP 1997-280789 19971014  
DT Utility  
LN.CNT 870  
INCL INCLM: 428/364.000  
INCLS: 428/394.000  
NCL NCLM: 428/364.000  
NCLS: 428/394.000  
IC [7]  
ICM: B02G003-00  
EXF 428/364; 428/394; 428/395; 264/205

L4 ANSWER 3 OF 8 USPATFULL  
AN 1999:33748 USPATFULL  
TI Photocurable formulation containing a partially polymerized  
divinylsiloxane linked bisbenzocyclobutene resin  
IN Foster, Pamela S., Midland, MI, United States  
Ecker, Ernest L., Midland, MI, United States  
Rutter, Jr., Edward W., Midland, MI, United States  
Moyer, Eric S., Midland, MI, United States  
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)  
PI US 5882836 19990316  
AI US 1995-465664 19950605 (8)  
RLI Division of Ser. No. US 1994-224203, filed on 14 Apr 1994 which is a  
continuation-in-part of Ser. No. US 1993-54999, filed on 29 Apr 1993  
DT Utility  
LN.CNT 1491  
INCL INCLM: 430/194.000  
INCLS: 430/286.100; 430/287.100; 522/065.000; 522/099.000  
NCL NCLM: 430/194.000  
NCLS: 430/286.100; 430/287.100; 522/065.000; 522/099.000  
IC [6]  
ICM: G03C001-52  
ICS: C08C002-48  
EXF 430/286; 430/287; 430/286.1; 430/287.1; 430/194; 522/99; 522/65  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L4 ANSWER 4 OF 8 USPATFULL  
AN 1998:162564 USPATFULL  
TI Partially polymerized divinylsiloxane linked bisbenzocyclobutene resins  
and methods for making said resins  
IN Foster, Pamela S., Midland, MI, United States  
Ecker, Ernest L., Midland, MI, United States  
Rutter, Jr., Edward W., Midland, MI, United States  
Moyer, Eric S., Midland, MI, United States  
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)  
PI US 5854302 19981229  
AI US 1994-224203 19940414 (8)  
RLI Continuation-in-part of Ser. No. US 1993-54999, filed on 29 Apr 1993,  
now abandoned  
DT Utility  
LN.CNT 1506  
INCL INCLM: 522/172.000  
INCLS: 526/281.000; 528/032.000; 556/453.000  
NCL NCLM: 522/172.000  
NCLS: 526/281.000; 528/032.000; 556/453.000  
IC [6]  
ICM: C08F002-46  
ICS: C08F010-08; C08G077-20  
EXF 522/172; 526/281; 528/32; 556/453; 428/391  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L4 ANSWER 5 OF 8 USPATFULL  
AN 97:96488 USPATFULL  
TI Flame-resistant heating body and method for making same  
IN Niibe, Akitoshi, Kamisu 3-7 29, Kamisu-cho, Kashima-gun, Ibaragi-ken,  
Japan  
Nakagawa, Kinichi, 1532 Koike-cho, Hamamatsu-City, Shizuoka-Pref, Japan  
PI US 5679277 19971021  
AI US 1995-398962 19950302 (8)  
DT Utility  
LN.CNT 593  
INCL INCLM: 219/543.000  
INCLS: 219/545.000; 219/482.000; 252/601.000  
NCL NCLM: 219/543.000  
NCLS: 219/482.000; 219/545.000; 252/601.000  
IC [6]  
ICM: H05B003-16  
ICS: H05B003-34; C09K021-00; B23K013-08  
EXF 219/211; 219/212; 219/213; 219/527; 219/528; 219/529; 219/543; 219/545;  
219/501; 219/482; 219/497; 252/601; 252/608; 252/609; 252/500; 252/502  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L4 ANSWER 6 OF 8 USPATFULL  
AN 96:116457 USPATFULL  
TI Oligomerized cyclobutarene resins  
IN Oaks, Frank L., San Carlos, CA, United States  
Moyer, Eric S., Midland, MI, United States  
Rutter, Jr., Edward W., Midland, MI, United States  
Harris, Robert F., Midland, MI, United States  
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)  
PI US 5585450 19961217  
AI US 1995-465666 19950605 (8)  
RLI Division of Ser. No. US 1994-290197, filed on 15 Aug 1994 which is a  
continuation-in-part of Ser. No. US 1991-805395, filed on 10 Dec 1991,  
now abandoned  
DT Utility  
LN.CNT 2009  
INCL INCLM: 526/279.000

INCLS: 526/284.000  
NCL NCLM: 526/279.000  
NCLS: 526/284.000  
IC [6]  
ICM: C08F130-08  
EXF 526/279; 526/284  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L4 ANSWER 7 OF 8 USPATFULL  
AN 96:80092 USPATFULL  
TI **Polybenzazole** fibers having improved tensile strength retention  
IN So, Ying H., Midland, MI, United States  
Martin, Steven J., Midland, MI, United States  
Chau, Chieh-Chun, Midland, MI, United States  
Wessling, Ritchie A., Midland, MI, United States  
Sen, Ashish, Midland, MI, United States  
Kato, Katsuhiko, Ikeda, Japan  
Roitman, Daniel B., Menlo Park, CA, United States  
Rochefort, Willie E., Corvallis, OR, United States  
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)  
PI US 5552221 19960903  
AI US 1994-366346 19941229 (8)  
DT Utility  
LN.CNT 938  
INCL INCLM: 428/373.000  
INCLS: 528/322.000; 528/327.000; 528/331.000; 528/340.000  
NCL NCLM: 428/373.000  
NCLS: 264/078.000; 264/129.000; 264/211.140; 264/211.150; 528/322.000;  
528/327.000; 528/331.000; 528/340.000  
IC [6]  
ICM: B32B005-02  
ICS: C08G073-22  
EXF 528/183; 528/322; 528/327; 528/331; 528/337; 528/340; 528/342; 428/373;  
264/331R  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L4 ANSWER 8 OF 8 USPATFULL  
AN 95:36005 USPATFULL  
TI Membranes having improved selectivity and recovery, and process for making same  
IN Jensvold, John A., Benicia, CA, United States  
Chary, Srikanth R., Fremont, CA, United States  
Jacks, Wendy S., Indianapolis, IN, United States  
Keller, Hans R., Concord, CA, United States  
Parker, Theodore L., Alpharetta, GA, United States  
Reddy, Damoder, Walnut Creek, CA, United States  
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)  
PI US 5409524 19950425  
AI US 1993-119800 19930910 (8)  
RLI Continuation-in-part of Ser. No. US 1992-989159, filed on 1 Dec 1992, now abandoned  
DT Utility  
LN.CNT 678  
INCL INCLM: 096/008.000  
INCLS: 095/045.000; 096/013.000; 096/014.000; 055/DIG.005  
NCL NCLM: 096/008.000  
NCLS: 055/DIG.005; 095/045.000; 096/013.000; 096/014.000  
IC [6]  
ICM: B01D053-22  
EXF 095/45; 095/47; 095/49; 095/51; 095/54; 096/4; 096/7-14; 055/524;  
055/528; 055/DIG.5  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

=> s polybenzazole# and (aromatic amine# or phenol?)

113 POLYBENZAZOLE#  
207726 AROMATIC  
203783 AMINE#  
15044 AROMATIC AMINE#  
(AROMATIC(W)AMINE#)  
162620 PHENOL?  
L5 35 POLYBENZAZOLE# AND (AROMATIC AMINE# OR PHENOL?)

=> s polybenzazole# and aromatic amine# and phenol?

113 POLYBENZAZOLE#  
207726 AROMATIC  
203783 AMINE#  
15044 AROMATIC AMINE#  
(AROMATIC(W)AMINE#)  
162620 PHENOL?  
L6 1 POLYBENZAZOLE# AND AROMATIC AMINE# AND PHENOL?

=> d

L6 ANSWER 1 OF 1 USPATFULL  
AN 92:80888 USPATFULL  
TI Copolymers containing polybenzoxazole, polybenzothiazole and  
polybenzimidazole moieties  
IN Harris, William J., Midland, MI, United States  
Hwang, Wen-Fang, Midland, MI, United States  
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)  
PI US 5151489 19920929  
AI US 1989-407973 19890915 (7)  
RLI Continuation-in-part of Ser. No. US 1989-378360, filed on 7 Jul 1989  
which is a continuation of Ser. No. US 1989-327925, filed on 23 Mar  
1989, now patented, Pat. No. US 5030706 which is a continuation-in-part  
of Ser. No. US 1988-256338, filed on 12 Oct 1988, now patented, Pat.  
No. US 5089568  
DT Utility  
LN.CNT 4017  
INCL INCLM: 528/183.000  
INCLS: 528/128.000; 525/410.000; 525/411.000; 525/413.000; 525/415.000;  
525/424.000; 525/425.000; 525/434.000  
NCL NCLM: 528/183.000  
NCLS: 525/410.000; 525/411.000; 525/413.000; 525/415.000; 525/424.000;  
525/425.000; 525/434.000; 528/128.000  
IC [5]  
ICM: C08G075-32  
EXF 528/128; 528/183; 525/410; 525/411; 525/413; 525/415; 525/424; 525/425;  
525/434  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.